

DX Short Pulse Series Nanosecond Lasers

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Photonics Industries' DX Series short pulse nanosecond lasers provide industrial systems with the most ideal compact form factor, short pulse width (down to ~ 10 ns), high power, high repetition rate (up to 1 MHz) Q-switched DPSS laser for high production throughput and precision quality. Specially patented intracavity harmonic generation, with no damaging indexing on the harmonic crystals, allows for higher performance and higher reliability, fulfilling demanding production criteria.



Applications

- Cutting, drilling, welding, scribing, marking, intra-marking, patterning, dielectric grooving, de-paneling, annealing, repair
- Reel to reel on-the-fly Converting Process Micromachining
- PCB/FPCB cutting, drilling, depaneling
- Silicon Wafer Scribing and Singulation, Low-k dielectric grooving
- Solar Cell Scribing and PERC processing
- Via Hole Drilling, Laser Trepanning, Laser Percussion Drilling
- Laser Lift-Off (LLO), Laser
 Debonding Systems, Semiconductor
 Microprocessing
- Selective Transfer of Light-emitting diodes (LED), μLED transfer assembly systems
- LIDAR Systems

Autonomous Systems, 3-D Scanning Systems, Airborne Laser Swath Mapping Systems, Laser Altimetry Systems

Features

Short pulse¹ at high powers:

Up to 50 W UV, ~12 ns, Up to >80 W Green, ~14 ns

High pulse energy:

Up to 1 mJ UV

Most versatile repetition rate range:

Single shot up to 1 MHz Green, Single shot up to >0.5 MHz UV

- Reliable, low COO, non-consumable design
 - Patented intracavity harmonic UV & Green generation, no damaging indexing of the harmonic crystals
- Industrialized, small form factor, ideal for compact integration
- Excellent TEM00 beam quality:

Typical M2 ≤ 1.1

Superior pulse stability:

Typical < 2 %

Total Pulse Control for ultimate integrability into systems:
 Duty Control to change output power while allowing

for longer pulse widths than the standard operating values

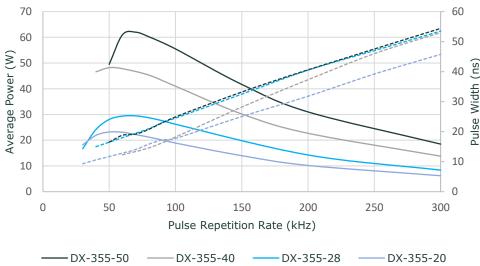
PEC (Power or Pulse Energy Control)

1. For longer pulse width models, please see the DX Long Pulse Series Nanosecond Lasers brochure

	DX-355-20	DX-355-28	DX-355-40	DX-355-50		
Beam ⁵ and output specific	ations					
Wavelength	355 nm					
Average power	20 W at 50 kHz	28 W at 50 kHz	40 W at 50 kHz	50 W at 50 kHz		
	18 W at 100 kHz	23 W at 100 kHz	40 W at 100 kHz	50 W at 100 kHz		
	10 W at 200 kHz	12 W at 200 kHz	25 W at 200 kHz	30 W at 200 kHz		
Pulse energy	~0.4 mJ	~0.6 mJ	~1 mJ	~1 mJ		
Pulse width	12±3 ns at 50 kHz					
	20±4 ns at 100 kHz					
Pulse repetition rate ¹	Single shot to 300 kHz (option up to >500 kHz)					
Pulse-to-pulse stability ²	< 2% rms					
Long term power stability ³	< ±2% rms					
Beam spatial mode	$TEM_{00} M^2 < 1.1$			$TEM_{00} M^2 < 1.2$		
Beam pointing stability	< 25 μrad					
Beam divergence	< 1.5 mrad					
Beam roundness	~90%					
Beam diameter ⁴ , at exit	~0.6 mm ~2			.5 mm		
Polarization ratio	Horizontal; >100:1					
Operational specifications	and system characteri	stics				
Interface	RS232, Ethernet, Software GUI, External TTL Triggering					
Warm-up time	< 15 minutes from standby, < 30 minutes from cold start					
Electrical requirement	100-240 V AC; or 32 V DC, 15 A					
Line frequency	50-60 Hz					
Ambient temperature	Ambient 15°C to 35°C (59°F to 95°F) Operating Range,					
,	Relative Humidity 90% Max., non-condensing					
Storage conditions	-10°C to 40°C; Sea Level to 12,000 m;					
	0% to 90% Relative Humidity, non-condensing					
Power consumption	< 240 W	< 320 W	< 420 W	< 600 W		
Dimensions (LxWxH)	18 x 7.5 x 3.75 in					
Weight	29 lbs (13.2 kg)					
Cooling system	Water-cooled					

^[1.] Lower pulse repetition rates (down to < 30 kHz) performance achieved by pulse energy capping. [2.] Measured at ambient temperature ± 2°C. [3.] Measured over 8 hours ± 1°C. [4.] Larger beam diameters at the exit (up to ~2.5 mm) are available with the expansion option. [5] Beam parameters are specified at pulse repetition rate of 70 kHz.







	DX-532-30	DX-532-48	DX-532-65	DX-532-80		
Beam and output specific	ations					
Wavelength	532 nm					
Average power	30 W, 100-200 kHz 27 W at 300 kHz 25 W at 400 kHz 22 W at 500 kHz	48 W, 100-500 kHz	65 W, 100-200 kHz 63 W at 300 kHz 60 W at 400 kHz 57 W at 500 kHz	>80 W, 100-200 kHz 65 W at 300 kHz 60 W at 400 kHz 55 W at 500 kHz		
Pulse energy	~0.5 mJ	~0.6 mJ	~0.7 mJ	~0.8 mJ		
Pulse width	10±2 ns at 50 kHz < 25 ns at 200 kHz		14±2 ns at 100 kHz < 25 ns at 200 kHz			
Pulse repetition rate ¹	Single shot to 500 kHz (option up to 1 MHz)					
Pulse-to-pulse stability ²	< 2% rms					
Long term power stability ³	< ±2% rms					
Beam spatial mode	$TEM_{00} M^2 < 1.1$		$TEM_{00} M^2 < 1.2$			
Beam pointing stability	< 25 µrad					
Beam divergence	< 2.5 mrad					
Beam roundness	~90%					
Beam diameter, at exit	~0.7 mm		~1 mm			
Polarization ratio	Vertical; >500:1					
Operational specifications	and system characteri	stics				
Interface	RS232, Ethernet, Software GUI, External TTL Triggering					
Warm-up time	< 15 minutes from standby, < 30 minutes from cold start					
Electrical requirement	100-240 V AC; or 32 V DC, 15 A					
Line frequency	50-60 Hz					
Ambient temperature	Ambient 15°C to 35°C (59°F to 95°F) Operating Range, Relative Humidity 90% Max., non-condensing					
Storage conditions	-10°C to 40°C; Sea Level to 12,000 m; 0% to 90% Relative Humidity, non-condensing					
Power consumption	< 24	40 W	< 320 W	< 420 W		
Dimensions (LxWxH)	16 x 7.5 x 3.75 in 18 x 7.5 x 3.75			18 x 7.5 x 3.75 in		
Weight	29 lbs (13.2 kg)					
Cooling system	Water-cooled					

^[1.] Lower pulse repetition rates (down to < 30 kHz) performance achieved by pulse energy capping. [2.] Measured at ambient temperature ± 2°C. [3.] Measured over 8 hours ± 1°C.

DX-532, Average power (W) and pulse width (ns) as a function of

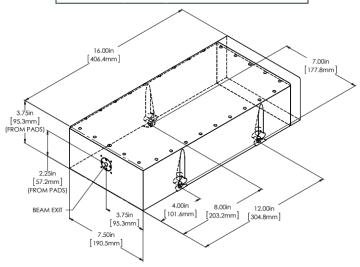
DX-532-80



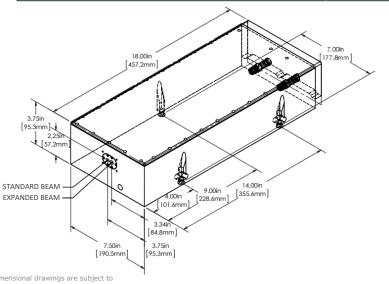
Pulse Repetition Rate (kHz) -DX-532-65 -DX-532-48 DX-532-30



DX-532-30, DX-532-48, DX-532-65



DX-355-20, DX-355-28, DX-355-40, DX-355-50, DX-532-80



Product specifications, characteristics, and dimensional drawings are subject to change without notice.

Photonics Industries conforms to provisions of US 21 CFR 1040.10 & 1040.11 and is made under one or more US patents listed below: 9,531,147, 8,817,831, 7,869,471, 7,346,092, 7,082,149, 7,079,557, 6,999,483, 6,980,574, 6,961,355, 6,842,293, 6,762,405, 6,690,692, 6,587,487, 6,584,134,6,366,596, 6,355,578, 6,327,281, 6,246,707, 6,229,829, 6,108,356, 6,061,370, 6,028,620, 5,936,983, 5,898,717 and Pending Patents

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<u>Photonics Industries International</u> is the pioneer of <u>intracavity harmonic lasers</u> and is at the forefront of developing, manufacturing and marketing a wide range of nanosecond, sub-nanosecond and femtosecond lasers for industrial, scientific, defense, and medical industries. Check out our <u>products</u> and see how we can help you <u>apply</u> our lasers to your needs.

